[FC1] Plasma & Atomic Layer Etching Ⅰ	
Date / Time	July 27 (Fri.), 2018 / 09:10-10:40
Place	Room C (#114)
Session Chair(s)	Eric A Joseph (IBM Thomas J. Watson Research Center, USA) Fred Roozeboom (Eindhoven Univ. of Tech., Netherlands)

FC1-1 [Keynote] **09:10-09:50**

Challenges to the Next Generation Semiconductor Equipment by Using Plasma

Kuntack Lee
Samsung Electronics Co., Ltd., Korea

FC1-2 **09:50-10:10**

Plasma-Assisted Atomic Layer Etching of Si-Based Dielectric Films Studied Using in Situ Surface Diagnostics

Sumit Agarwal[1], Ryan J. Gasvoda[1], Scott Wang[2], Ranadeep Bhowmick[2], and Eric A. Hudson[2]
[1]*Colorado School of Mines, USA,* [2]*Lam Research Corporation, USA.*

FC1-3 [Invited] **10:10-10:40**

Frontiers of Industrial Application of Atomic Layer Etching

Alok Ranjan[1] and Peter Ventzek[2]
[1]*TEL Tech. Center, America, LLC, USA,* [2]*Tokyo Electron America, Inc., USA*